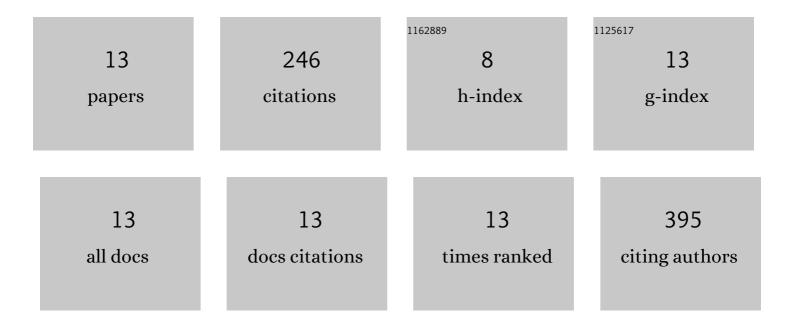
Sylwia Klejna

List of Publications by Year in descending order

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SVINIA KIEINA

#	ARTICLE	IF	CITATIONS
1	Reversible Cationâ€Mediated Anionic Redox in Defect Spinel Structure for High Power Batteries. Advanced Functional Materials, 2022, 32, 2108278.	7.8	3
2	Supercapacitance in graphene oxide materials modified with tetrapyrrole dyes: a mechanistic study. Nanoscale, 2022, 14, 8534-8547.	2.8	1
3	Halogen-containing semiconductors: From artificial photosynthesis to unconventional computing. Coordination Chemistry Reviews, 2020, 415, 213316.	9.5	21
4	Structural and electronic properties of multifunctional carbon composites of organometal halide perovskites. Journal of Materials Chemistry A, 2019, 7, 25020-25031.	5.2	8
5	Fluorimetric naphthalimide-based polymer logic beads responsive to acidity and oxidisability. Journal of Materials Chemistry C, 2019, 7, 15225-15232.	2.7	21
6	Molecular engineering of logic gate types by module rearrangement in â€~Pourbaix Sensors': the effect of excited-state electric fields. Organic and Biomolecular Chemistry, 2018, 16, 6195-6201.	1.5	23
7	Heavy pnictogen chalcohalides: the synthesis, structure and properties of these rediscovered semiconductors. Chemical Communications, 2018, 54, 12133-12162.	2.2	39
8	Electronic sensitization of CuO thin films by Cr-doping for enhanced gas sensor response at low detection limit. Materials Research Express, 2018, 5, 126406.	0.8	34
9	Triiodide Organic Salts: Photoelectrochemistry at the Border between Insulators and Semiconductors. ChemElectroChem, 2018, 5, 3486-3497.	1.7	8
10	Decomposition of Metal Alkylamides, Alkyls, and Halides at Reducible Oxide Surfaces: Mechanism of â€~Clean-up' During Atomic Layer Deposition of Dielectrics onto Ill–V Substrates. Chemistry of Materials, 2014, 26, 2427-2437.	3.2	16
11	Mechanisms for Substrate-Enhanced Growth during the Early Stages of Atomic Layer Deposition of Alumina onto Silicon Nitride Surfaces. Chemistry of Materials, 2012, 24, 1080-1090.	3.2	17
12	First-Principles Modeling of the "Clean-Up―of Native Oxides during Atomic Layer Deposition onto III–V Substrates. Journal of Physical Chemistry C, 2012, 116, 643-654.	1.5	50
13	Understanding 'Clean-Up' of Ill–V Native Oxides During Atomic Layer Deposition Using Bulk First Principles Models. Journal of Nanoscience and Nanotechnology, 2011, 11, 8246-8250.	0.9	5